Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S2	2503	427/248.1.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/19 13:35
S3	237	427/255.23.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/19 13:35
<b>S4</b>	934	427/255.7.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/19 13:35
S5	232	S2 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 14:14
<b>S6</b>	25.	S3 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 13:36
S7	45	S4 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 13:53
<b>S11</b>	143	chang-mei.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 13:50
S12	158	chen-ling.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 13:52

S14	157	bis(allyl)palladium or bis(2-methylallyl)palladium or (cyclopentadienyl)(allyl)palladium or trimethyl(cyclopentadienyl)platinum	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 14	10
		or trimethyl(methylcyclopentadienyl)pl atinum or (cyclopentadienyl)(allyl)platinum or dimethyl(cyclooctadiene)platinum					
		or methyl(carbonyl)cyclopentadienylpl atinum or trimethyl(acetylacetonato)platinum					
		or bis(acteylactonato)platinum or (cyclopentadienyl)(cyclohexadienyl) cobalt or (cyclobutadienyl)(cyclopentadienyl)					
		cobalt or bis(cyclopentadienyl)cobalt or bis(methylcyclopentadienyl)cobalt or cyclopentadenyl(1,					
		3-hexadienyl)cobalt or (cyclopentadienyl)(5-methylcyclope ntadienyl)cobalt or bis(ethylene)(pentamethylcyclopent				,	*
		adienyl)cobalt or bis(methylcyclopentadienyl)nickel or bis(propylene)rhodium or bis(carbonyl)(cyclopentadienyl)rhodi					
	,	um or bis(carbonyl)(methylcyclopentadien yl)rhodium or bis(carbonyl)(ehtylcyclopentadienyl)					
		rhodium or (bis(allyl) palladium) or (bis(2-methylallyl) palladium) or ((cyclopentadienyl)(allyl) palladium) or trimethyl(cyclopentadienyl)					
		platinum or trimethyl(methylcyclopentadienyl) platinum or (cyclopentadienyl)(allyl) platinum or dimethyl(cyclooctadiene) platinum					
		or methyl(carbonyl)cyclopentadienyl platinum or trimethyl(acetylacetonato) platinum or bis(acteylactonato) platinum or				·	
		(cyclopentadienyl)(cyclohexadienyl) cobalt or (cyclobutadienyl)(cyclopentadienyl) cobalt or bis(cyclopentadienyl)					ō
		cobalt or bis(cyclopentadienyl) cobalt or bis(methylcyclopentadienyl) cobalt or cyclopentadenyl(1,3-hexadienyl) cobalt or					
	06 1:06:44 PM ments and Set	(cyclopentadienyl)(5-methylcyclopentadienyl) cobalt or	spaces\1081123	0.wsp		Pa	ige 2
	•	his/methylovolonentadienyl) nickel			!		

S15		S14 and (silane or disilane or dimethylsilane or methyl silane or methylsilane or ethylsilane or ethylsilane or borane or diboran or triborane or tetraborane or pentaborane or hexaborane or heptaborane or octaborane of nanoborane or decaborane or "sih. sub.4" or "sis.sub.2h.sub.4" or "sic. sub.2.sub.8" or "sich.sub.6" or "sic. sub.2h.sub.8" or "bh.sub.3" or "b. sub.2h.sub.6" or "b.sub.3h.sub.9" or "b.sub.4h.sub.12" or "b.sub.5h. sub.15" or "b.sub.6h.sub.18" or "b. sub.7h.sub.21" or "b.sub.8h.sub.24" or "b.sub.9h.sub.27" or "b.sub.10h. sub.30")	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 14:22
S20	113597	(palladium or pd or platinum or pt	US-PGPUB;	ADJ	ON	2006/09/19 14:24
		or cobalt or co or nickel or ni or rhodium or rh) and (silane or disilane or disilane or methylsilane or methylsilane or methylsilane or ethylsilane or ethylsilane or diboran or triborane or tetraborane or pentaborane or hexaborane or heptaborane or octaborane or heptaborane or decaborane or "sih. sub.4" or "si.sub.2h.sub.4" or "sic. sub.2.sub.8" or "sich.sub.6" or "sic. sub.2h.sub.8" or "bh.sub.3" or "b. sub.2h.sub.9" or "b.sub.3h.sub.9" or "b.sub.4h.sub.12" or "b.sub.5h. sub.15" or "b.sub.6h.sub.18" or "b. sub.7h.sub.21" or "b.sub.8h.sub.24"	USPAT; DERWENT; IBM_TDB			
74.200 x 1		or "b.sub.9h.sub.27" or "b.sub.10h.				
1 4 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1		sub.30")				
S21	1133	S20 and ((atomic layer deposition) or ald or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/19 14:32
S33	. 2	("6527855").PN.	US-PGPUB;	OR	OFF	2006/09/20 08:03
7			USPAT;			
- 13.	9 1)		DERWENT; IBM_TDB	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1		
S34	2503	427/248.1.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 08:03

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S35	232	S34 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON ·	2006/09/20 08:03
S37	237	427/255.23.ccls.	US-PGPUB; USPAT; DERWENT;	OR	ON	2006/09/20 08:03
			IBM_TDB		<b>李</b> 斯特第	
S38	25	S37 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 08:03
S40	934	427/255.7.ccls.	US-PGPUB;	OR	ON A	2006/09/20 08:03
			USPAT; DERWENT; IBM_TDB			
S41	45	S40 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 08:03
S42	- 2503	-427/248.1.ccls.	US-PGPUB;	OR	ON MA	2006/09/20 10:23
			USPAT; DERWENT; IBM_TDB			
S43	232	S42 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON .	2006/09/20 10:28
S44	37	S43 and (ruthenium ru)	US-PGPUB;	OR 👯 🔭	ON :	2006/09/20 10:23
			USPAT; DERWENT; IBM_TDB			
S45	237	427/255.23.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 10:23
S46	25	S45 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:23
S47	4	S46 and (ruthenium ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 10:23

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S48	934	427/255.7.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 10:23
S49	45	S48 and ((atomic layer deposition) or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd)))	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:23
S50	4	S49 and (ruthenium ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	OR	ON	2006/09/20 10:23
S51	<b>554</b>	((atomic layer deposition) or ald or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd))) same (ruthenium or ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 14:08
S54	10	S51 and (2, 4-dimethylpentadienyl\$20)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 13:23
S55	481	S51 and reduc\$4	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:36
S56	29	ganguli-seshadri.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:34
S57	15	maity-nirmalya.in.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 10:34
S58	5	("20030037802"   "5372849"   "6003526"   "6074945"   "6537461").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2006/09/20 10:48
S59	554	((atomic layer deposition) or ald or (cyclical deposition) or (sequential ((vapor deposition) or (chemical vapor deposition) or cvd))) same (ruthenium or ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 13:23
560	10	S59 and (\$10methylpentadienyl\$20)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 13:24

S61	113	S59 and (\$15pentadienyl\$20)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 13:25
S62	13	S59 and (expanding with channel)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/20 14:09
S63	316	S59 and (chamber or apparatus)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ .	ON	2006/09/20 14:10
S64	4	shah-kavita.in.	US-PGPUB; USPAT; DERWENT; IBM TDB	ADJ	ON	. 2006/09/21 08:16
S65	715	427/255.28.ccls.	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:16
S66	20	S65 and (atomic layer deposition or ald) and (ruthenium or ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:29
S67	558	(atomic layer deposition or ald) same (ruthenium or ru)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON .	2006/09/21 08:30
<b>S68</b>	473	S67 and (barrier layer or tantalum or tantalum nitride or tantalum silicon nitride or titanium or titanium nitride or titanium silicon nitride or tungsten or tungsten nitride)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:42
S69	111	S68 and resistivity	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:33
S70	20	S68 and sheet resistance	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:44
S71	104	S67 and (barrier layer with copper)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:42

S72	421	S67 and (tantalum or tantalum nitride or tantalum silicon nitride or titanium or titanium nitride or titanium silicon nitride or tungsten or tungsten nitride)	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	ON	2006/09/21 08:42
S73	22	S67 and sheet resistance	US-PGPUB; USPAT; DERWENT; IBM_TDB	ADJ	e e	2006/09/21 08:44